



Application Serial No. 10/815,065
Filing Date March 30, 2004
Inventor Sujit Sharan, et al.
Assignee Micron Technology, Inc.
Group Art Unit 2891
Examiner G. Lee
Attorney's Docket No. MI22-1421
Title: Methods of Forming Silicon Dioxide Layers, and Methods of Forming
Trench Isolation Regions

RESPONSE TO AUGUST 8, 2005 OFFICE ACTION

To: Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

From: James E. Lake (Tel. 509-624-4276; Fax 509-838-3424)
Wells St. John P.S.
601 W. First Avenue, Suite 1300
Spokane, WA 99201-3828

AMENDMENTS

No amendments.

EV 550718362